

# Digital Integrated Circuit (IC) Layout and Design - Week 10, Lecture 20

- Midterm Due in Class
- Dynamic Logic
- SRAM
- Wrap up

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## Clocked CMOS Logic (C<sup>2</sup>MOS)

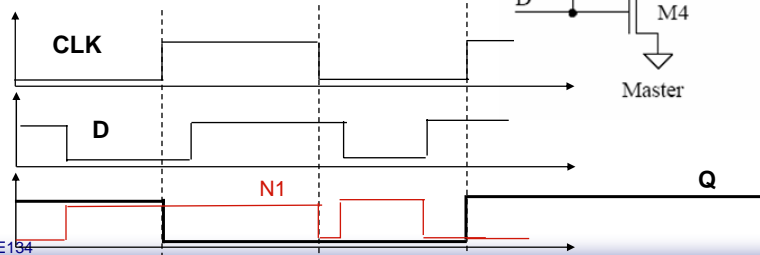
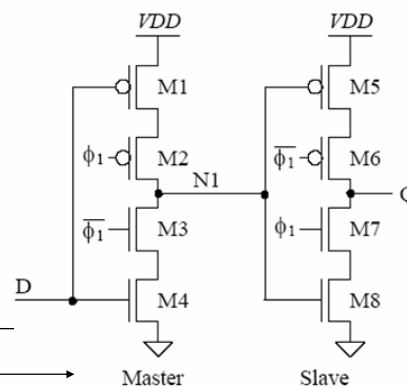
### □ Clocked CMOS Register (Positive Edge)

$\phi_1$  low:

- Master enabled.  $N1 = \overline{D}$ . M1 & M3 on.
- Slave latched. M6 and M7 off. Output Q is in charge storage mode (floating). Hi-Z state (high impedance).

$\phi_1$  high:

- Master Hi-Z state (N1 floating  $\overline{D}_n$ ).
- Slave enabled.  $Q_{n+1} = D_n$ .

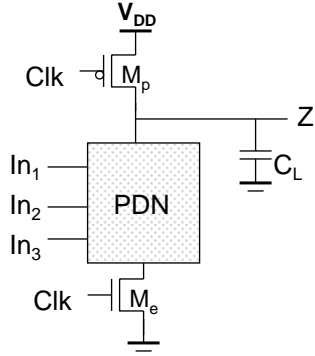


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# C<sup>2</sup>MOS: Precharge – Evaluate (PE) Logic

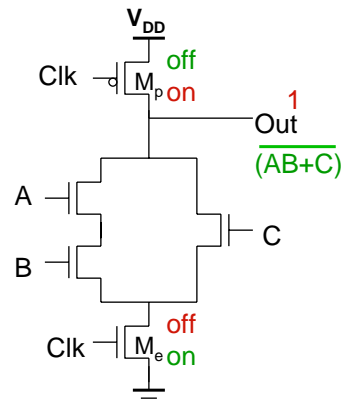
## General Concept



**CLK = 0:** Precharge output  $Z = V_{DD}$ .  
 $M_e$  off;  $M_p$  on.  $Z = V_{DD}$ .

**CLK = 1:** Evaluate.  $M_p$  off.  $M_e$  on.  
 Pull down Z (or not) depending on logic implemented in PDN.

## Specific Example



**CLK = 0:** Precharge  $Z = 1$

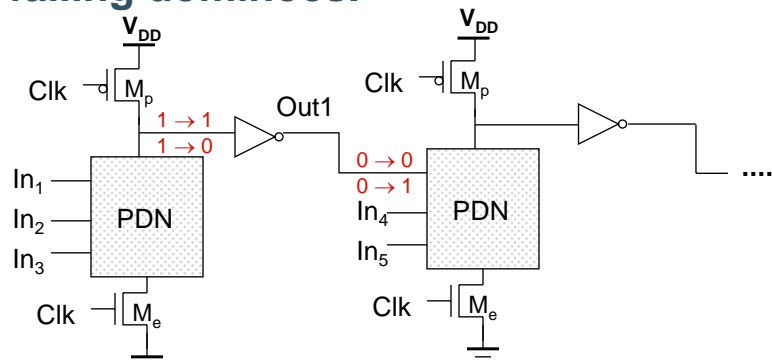
**CLK = 1:** Evaluate.  $Z = (AB + C)$

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# Domino Logic

□ Like falling dominoes.



**CLK=0:** Precharge

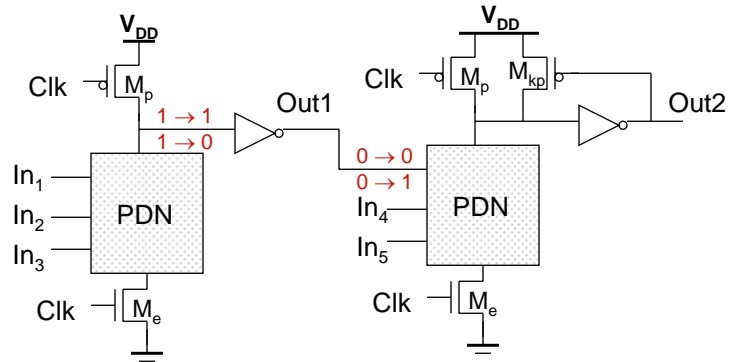
**CLK=1:** Logic propagates thru series of gates like dominoes falling.

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# Domino Logic with Keeper at output

□ Use small  $M_{kp}$

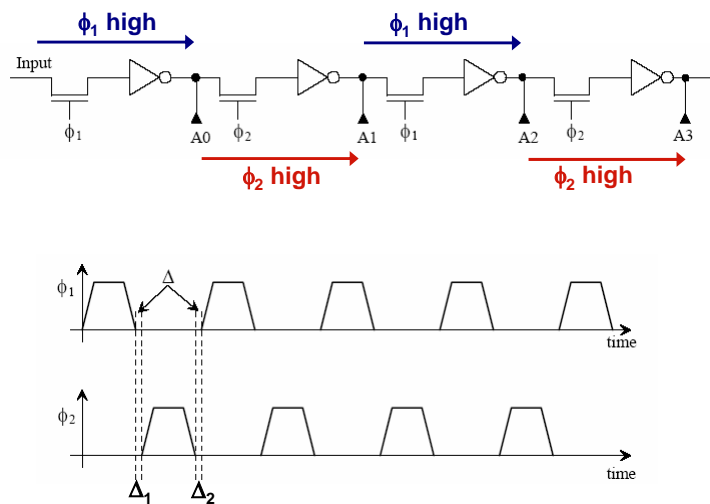


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# Dynamic Shift Register

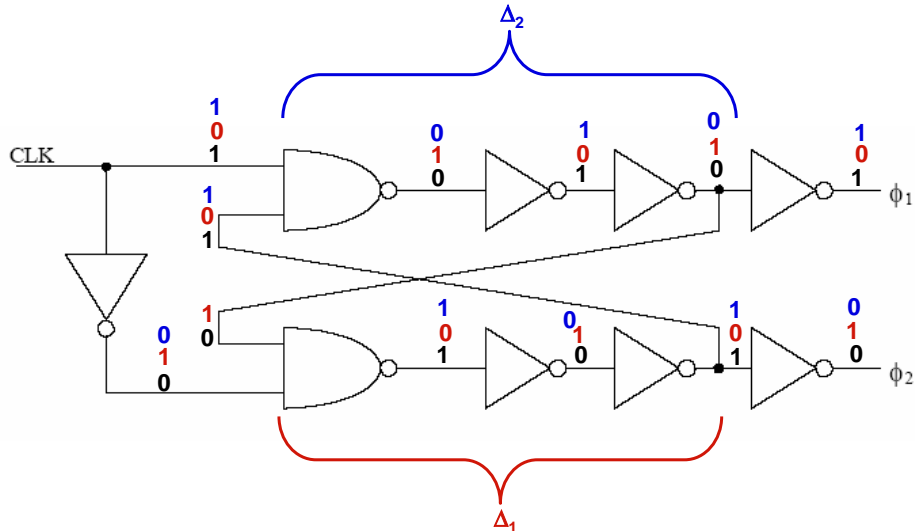
□ Non-overlapping clock



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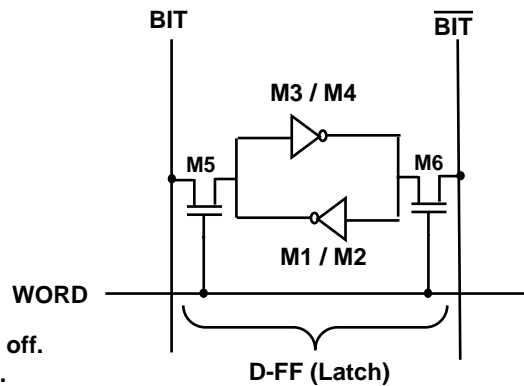
# Non-Overlapping CLK



Initially, CLK=1 (Black).  $\phi_1 = 1$  &  $\phi_2 = 0$ .  
 CLK  $\rightarrow$  0 (Red)  
 CLK  $\rightarrow$  1 (Blue)

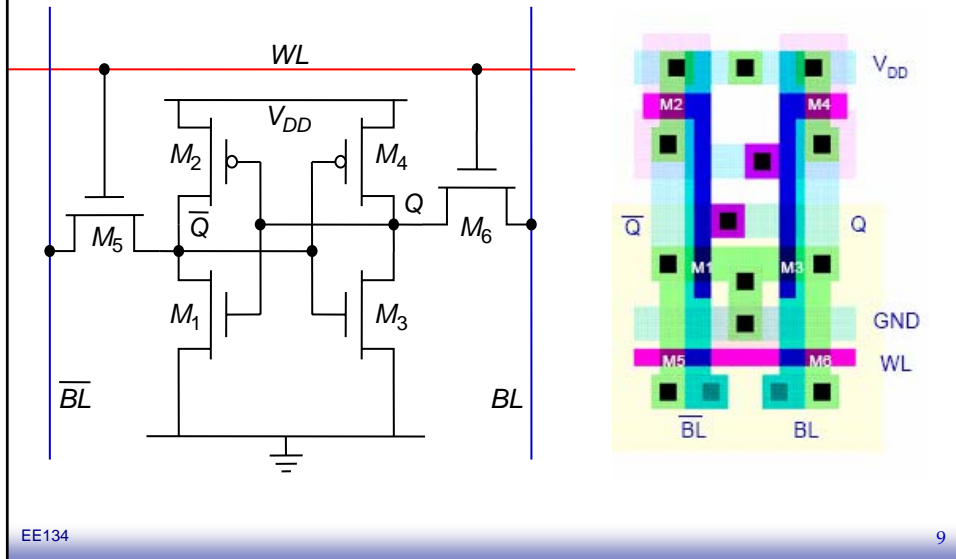
# Static RAM (SRAM)

## SRAM Cell: Simple D-FF (Latch)



- Word line low
  - Pass transistors M5 and M6 off.
  - Data latched in inverter pair.
- Word line high: Writing / Reading
  - Writing: Write by force.
  - Reading: BIT and  $\overline{\text{BIT}}$  precharged to either  $V_{DD}$  or  $V_{DD}/2$ . Read.

## SRAM at transistor level



## EE134 Summary

### □ Major Challenges

- Cost
- Power Consumption
- Robustness
- Complexity

□ Some new circuit solutions and design methodologies are coming.

# Technology Scaling

	2004	2006	2008	2010	2012	2014	2016	2018
Technology Node (nm)	90	65	45	32	22	16	11	8
Integration Capacity (BT)	0.5	1	2	4	8	16	32	64
Delay = CV/I scaling	0.7	~0.7	>0.7	Delay scaling will slow down				
Energy/Logic Op scaling	>0.35	>0.5	>0.5	Energy scaling will slow down				
Bulk Planar CMOS	High Probability			Low Probability				
Alternate, 3G etc	Low Probability			High Probability				
Variability	Medium			High		Very High		
ILD (K)	~3	<3	Reduce slowly towards 2-2.5					
RC Delay	1	1	1	1	1	1	1	1
Metal Layers	6-7	7-8	8-9	0.5 to 1 layer per generation				

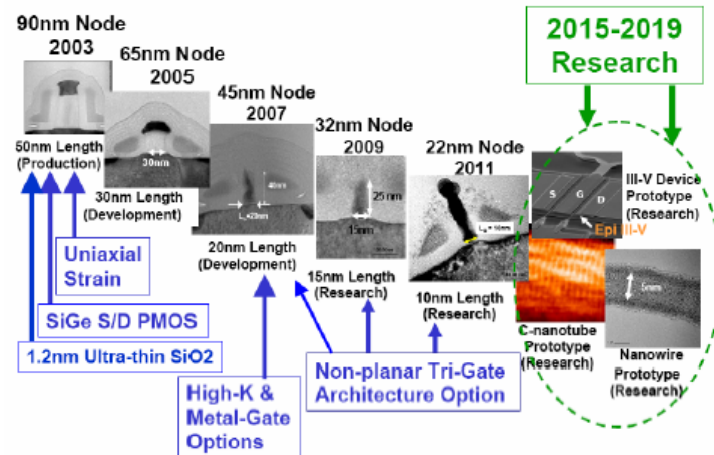
Courtesy: R. Krishnamurthy (Intel)

Internal University

FCRP(MARCO)

SRC

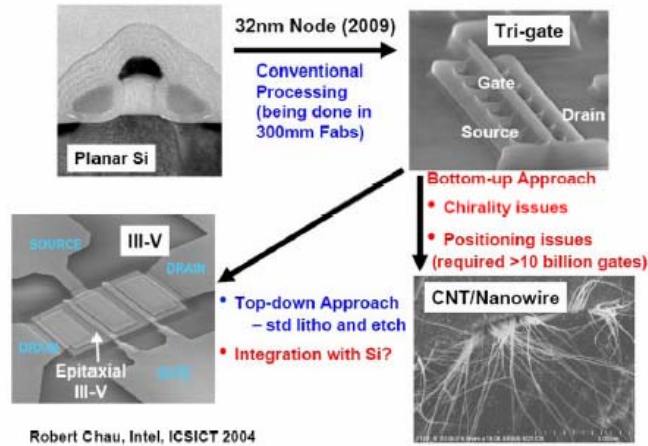
# Research Roadmap



Robert Chau, Intel, ICSICT 2004

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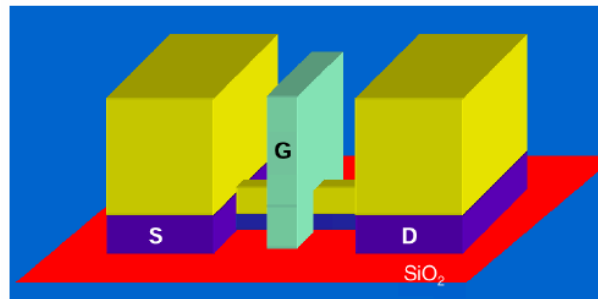
# Device Evolution



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# 25 nm FinFET



25 nm MOS transistor (Folded Channel)

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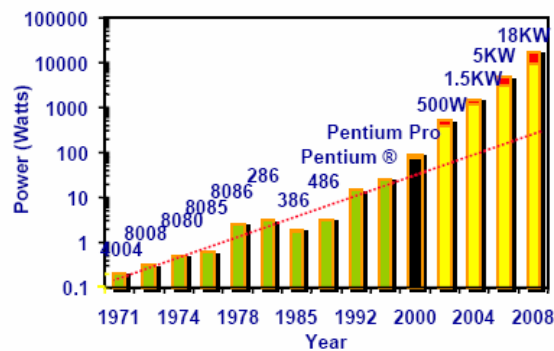
## Cost

- ❑ Mask cost in 90nm technology is over \$1M.
- ❑ Bugs are very expensive.
- ❑ Design effort increases in DSM.
- ❑ Cost of new tools.
- ❑ Non-recurring costs dominate the price effectiveness of low-volume ASICs.
- ❑ Need to have a product that can fit multiple applications, customers (flexibility).

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## Power has become a Problem



Source:  
S. Borkar  
(Intel)

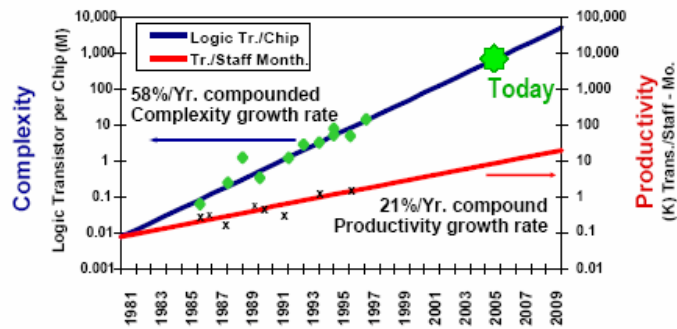
Power delivery and dissipation will be prohibitive

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# The Productivity Gap



Source: Sematech

Complexity outpaces design productivity

# Challenges in Digital Design

## □ The Deep Submicron (DSM) Effect

$\propto$  DSM

### “Microscopic Problems”

- Ultra-high speed design
- Interconnect
- Noise, Crosstalk
- Reliability, Manufacturability
- Power Dissipation
- Clock distribution.

Everything Looks a Little Different

$\propto$  1/DSM

### “Macroscopic Issues”

- Time-to-Market
- Millions of Gates
- High-Level Abstractions
- Reuse & IP: Portability
- Predictability
- etc.

...and There's a Lot of Them!



## ABET Evaluation: Course Objectives

### □ Things that you should have learned in EE134.

	<u>Course Objective</u>	Very Poorly				Very Well
1	Understand the device model for a modern short-channel FET.	1	2	3	4	5
2	Understand the parasitic diodes and capacitors of an inverter.	1	2	3	4	5
3	Ability to layout, DRC, and LVS a CMOS digital IC.	1	2	3	4	5
4	Calculate delay times through inverters and logic gates.	1	2	3	4	5
5	Size a chain of inverters to drive a large capacitive load.	1	2	3	4	5
6	Design static CMOS logic gates.	1	2	3	4	5
7	Understand CMOS transmission gates.	1	2	3	4	5
8	Understand CMOS transmission gate latches and registers.	1	2	3	4	5

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## ABET: Program Outcomes

	<u>Attribute</u>	Very Poorly				Very Well
<b>a</b>	An ability to apply knowledge of mathematics, science, and engineering	1	2	3	4	5
<b>b</b>	An ability to design and conduct experiments, as well as to analyze and interpret data	1	2	3	4	5
<b>c</b>	An ability to design a system, component, or process to meet desired needs	1	2	3	4	5
<b>d</b>	An ability to function on multi-disciplinary teams	1	2	3	4	5
<b>e</b>	An ability to identify, formulate, and solve engineering problems	1	2	3	4	5
<b>f</b>	An understanding of professional ethical responsibility	1	2	3	4	5
<b>g</b>	An ability to communicate effectively	1	2	3	4	5
<b>h</b>	The broad education necessary to understand the impact of engineering solutions in a global and societal context	1	2	3	4	5
<b>i</b>	A recognition of the need for, and an ability to engage in life-long learning	1	2	3	4	5
<b>j</b>	A knowledge of contemporary issues	1	2	3	4	5
<b>k</b>	An ability to use the techniques, skills, and modern engineering tools necessary for engineering practice	1	2	3	4	5

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